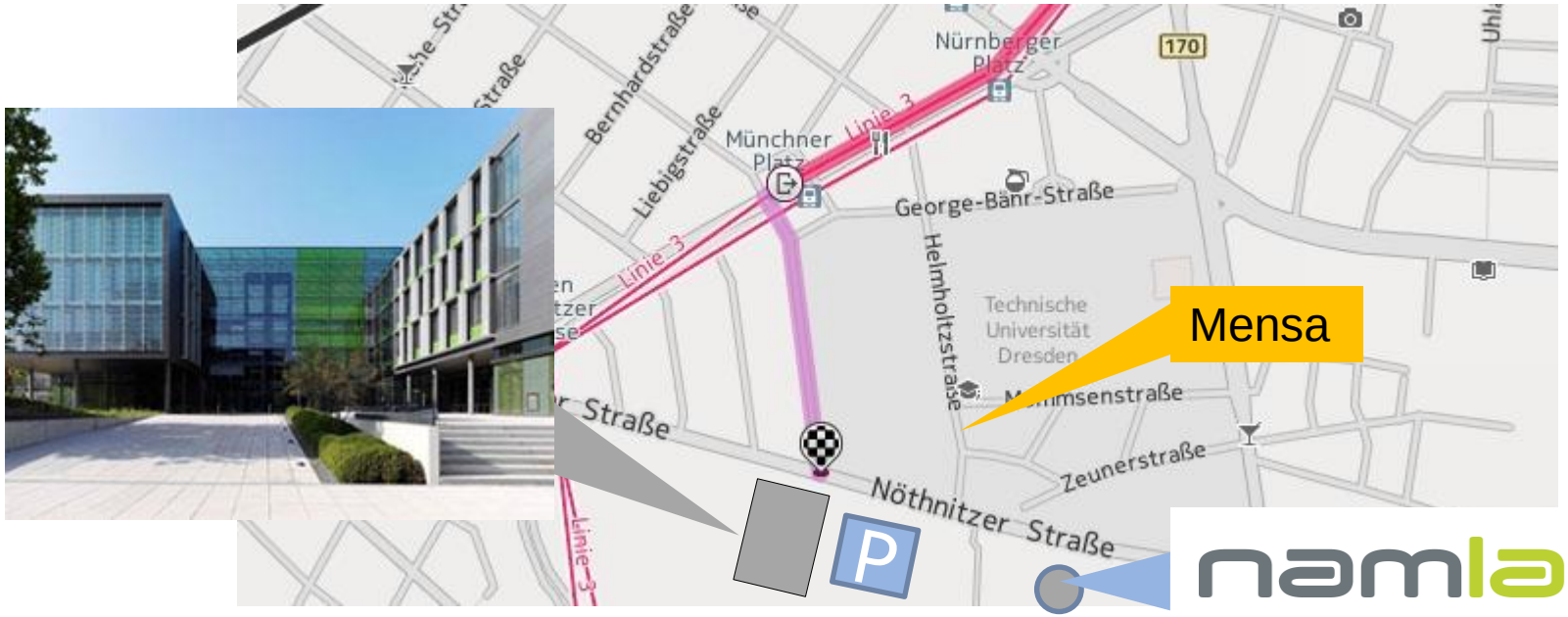
Agenda

	Time	Presenter	Institute	Title of Presentation
	9:00	T. Mikolajick/ U. Schroeder	Namlab	Welcome
		Device	*chair: U. Schroeder*	
1	9:15	E. Erben	GlobalFoundries	HKMG Reliability
2	9:35	M. Drescher	Fraunhofer IPMS-CNT	Surface treatments for enhanced reliability in 28nm HKMG
3	9:55	D. Triyoso	GlobalFoundries	ALD Spacer for HKMG
4	10:15	M. Tallarida	BTU Cottbus	III-V/Oxide Interfaces Investigated with Synchrotron Radiation PE Spectroscopy
5	10:35	A. Freese	Namlab	Molecular beam deposited ZrO2 as a high k dielectric for future GaN power devices
		Coffee break: 10:50 - 11:10h		
		Non volatile memory	*chair: U. Schroeder*	
6	11:10	P. Polakowski	Fraunhofer IPMS-CNT	Alternative dopants for stabilizing Ferroelectric HfO2 in planar MIM-stacks
7	11:30	T. Schenk	Namlab	Electric Field Cycling Behavior of Ferroelectric Sr:HfO2
8	11:45	S. Starschich	RWTH Aachen IWE2	Low temperature switching behavior of doped HfO2
9	12:05	R. Materlik	Hochschule München	Simulation of ferroelectric doped HfO2
		Lunch - Alte Mensa (Helmholtz Strasse): 12:25 - 13:30h		

Enjoy Lunch☺

For your lunch ticket you will get:

one main dish
+ one dessert
+ one drink



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		Lunch - Alte Mensa (Helmholtz Strasse): 12:25 - 13:30h		
		RRAM	*chair: S. Slesazeck*	
10	13:30	T. Bertaud	IHP Frankfurt/Oder	HfO2 based RRAM for embedded non-volatile memory
11	13:50	U. Böttger	RWTH Aachen IWE2	From soft breakdown to resistive switching
12	14:10	S. Spiga	MDM Agrate Brianza	Resistive switching in doped-HfO2
13	14:30	K. Fröhlich	U. Bratislava	Resistive switching in oxide based metal-insulator-metal structures: TiO2, HfO2
14	14:50	H. Wylezich	Namlab	Tuning Nb2O5 for Resistive Switching by Ion Implantation
		Capacitor		
15	15:05	W. Weinreich	Fraunhofer IPMS-CNT	3D MIM Capacitors with improved reliability for SoC and SiP applications
		Coffee break: 15:25 - 15:45h		
		Solar/OLED	*chair: I. Dirnstorfer*	
16	15:45	E. Kessels	TU Eindhoven	ALD of oxides for silicon photovoltaics
17	16:05	A. Schmid	TUBA Freiberg	Defect characterization and passivation characterisitcs of high k materials
18	16:25	F. Benner	Namlab	Effects of Ti-doping on the passivation effect of Al2O3 thin film layers
19	16:40	C. Hossbach	IHM	ALD and MLD barrier layers for OLED and OPV
	17:00	End		